

Conference Background

The EIPBN Conference is recognized as the foremost international meeting dedicated to lithographic science and process technology and its use in micro and nanofabrication techniques and their applications. The conference brings together engineers and scientists from industries and universities from all over the world to discuss recent progress and future trends.

Meeting Format

The conference opens on Tuesday afternoon with a special commercial session which features vendors of materials and equipment relevant to the conference. The plenary session is on Wednesday morning. The remainder of the conference is organized in three parallel sessions. The length of presentation and discussion is 30 minutes for invited papers and 20 minutes for contributed papers.

A special feature of the technical program is the poster session that includes invited and contributed papers. There is only one poster session, but posters will be displayed for informal viewing throughout the entire conference. No distinction is made between the importance of poster and oral presentations.

Technical Scope

Abstracts representing high quality original research are invited in the following areas:

- Extreme UV lithography
- Electron and ion beam lithography
- Advanced optical lithography
- Metrology and imaging
- Resists and resist processingPlasma etching and deposition
- Nano-fabrication techniques
- Maskless lithography
- Nano-imprint lithography
- Soft lithography and embossing

Topics in emerging technologies include:

- Simulation and modelling for the nano-scale
- Nano-photonics
- Patterned media and data storage
- Nano-electronics
- Nano-biology
- Micro- and nano-scale MEMS
- Micro- and nano-fluidics
- Self-assembly and directed self-assembly
- Nanofabrication for energy sources
- Atomic and Molecular manipulation

Conference Registration

We strongly encourage you to register on line by using our website www.eipbn.org Early registration and special student rates are available. The early registration deadline is May 16, 2013.

Conference Location

The conference will be held at the Gaylord Opryland Resort and Convention Center, just East of Nashville, Tennessee. The Gaylord Opryland boasts nine acres of indoor gardens, cascading waterfalls, the longest indoor river, contemporary restaurants, unique shopping experiences, a 20,000-square-foot spa and fitness center, pools, and an award winning Scottish links-style, par-72 golf course.

Gaylord Opryland Resort and Convention Center

2800 Opryland Drive Nashville, TN 37214 USA Phone: 1-615-889-1000

Fax: 1-615-871-7741

http://www.gaylordhotels.com/gaylord-opryland/

On-line hotel registration will be available on the EIPBN website

Abstract Submission

Abstracts should be submitted online at

www.eipbn.org

Abstracts are limited to one page of text (12 point or larger type) and a second, optional page with up to four figures.

Abstract deadline: January 7, 2013

Late submissions may be considered but only if they report truly outstanding results. Please prepare abstracts carefully and describe accomplishments specifically. Authors will be notified of acceptance by April 11, 2013. Earlier notification will be provided to those authors providing an e-mail address.

Micrograph Contest

On a less technical level, EIPBN offers the opportunity to immortalize your favorite micrograph(s). Categories and previous winners are described on our website.

Manuscript Submission

Manuscripts must be submitted around the time of the conference and will be subjected to a critical peer review before they can be accepted for publication in the Nov/Dec 2013 issue of the Journal of Vacuum Science and Technology. Please note that authors are required to pay a publication charge of about \$100 per page.

Student Support

Limited funds are available to support student travel. The Conference Chair must receive a letter requesting support from the student's advisor by May 1, 2013. For helping with housing costs a "Room with another student" option will be available at the Gaylord.

Conference Chair

Leonidas E. Ocola PhD Nanofabrication Group Center for Nanoscale Materials Argonne National Laboratory 9700 South Cass Ave. Bldg 440 Rm A129 Argonne, IL 60439 Phone: 1-630-252-6613

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Program Chair

Professor Rebecca Cheung Scottish Microelectronics Centre School of Engineering West Mains Road University of Edinburgh EH9 3JF United Kingdom

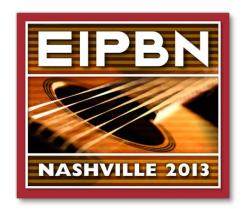
Phone: ++ 44 131 650 5749 Email: <u>r.cheung@ed.ac.uk</u> or eipbn13program@gmail.com

To add your name to the mailing list, please mail a business card or e-mail to the Conference Chair.

Other Information

The EIPBN conference is incorporated as a nonprofit organization in the state of New Jersey and is cosponsored by the American Vacuum Society (www.avs.org), in cooperation with the IEEE Electron Devices, Lasers and Electro-optics Societies and the Optical Society of America. It is organized by a steering committee that elects two new members each year from those that regularly attend the conference.

Call for Papers



The 57th International Conference on Electron, Ion, and Photon Beam Technology, and Nanofabrication

May 28 - 31, 2013

www.eipbn.org

Gaylord Opryland Resort and Convention Center

